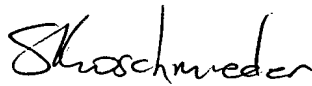


REMARKS

Claims 1-20 are active in the present application. Claims 6-9, 12-14 and 16-20 have been amended to remove multiple dependencies. No new matter is added. An action on the merits and allowance of claims is solicited.

Respectfully submitted,

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IN THE CLAIMS

--6. (Amended) The crosslinked resin as claimed in [one of claims 1 to 5] claim 1, characterized in that the acid is acetic acid.

7. (Amended) The crosslinked resin as claimed in [one of claims 1 to 5] claim 1, characterized in that the acid is propanoic acid.

8. (Amended) The crosslinked resin as claimed in [one of claims 1 to 5] claim 1, characterized in that the acid is trifluoroacetic acid.

9. (Amended) The crosslinked resin as claimed in [one of claims 1 to 8] claim 1, characterized in that it additionally comprises at least one photoinitiating agent.

12. (Amended) The process for the manufacture of ceramic or of glass as claimed in [either of claims 10 and 11] claim 10, characterized in that the simple metal alkoxides are zirconium alkoxide or titanium alkoxide.

13. (Amended) The process for the manufacture of ceramic or of glass as claimed in [either of claims 10 and 11] claim 10, characterized in that it comprises a stage of preparation of complex metal alkoxides from lead carboxylate, zirconium alkoxide and titanium alkoxide.

14. (Amended) The process for the manufacture of ceramic or glass patterns at the surface of a substrate as claimed in [one of claims 10 to 13] claim 10, characterized in that:

- exposure to radiation is carried out through a mask, so as to define radiation-exposed patterns and non-radiation-exposed patterns;

- it comprises the dissolution of the non-radiation-exposed patterns in a solvent.

16. (Amended) The process for the manufacture of a ceramic or of a glass as claimed in [one of claims 10 to 15] claim 10, characterized in that the substrate is glass.

17. (Amended) The process for the manufacture of a ceramic or of a glass as claimed in [one of claims 10 to 15] claim 10, characterized in that the substrate is silicon.

18. (Amended) A capacitor, characterized in that it is obtained from the process for the manufacture of a ceramic or of a glass as claimed in [one of claims 10 to 15] claim 10.

19. (Amended) A piezoelectric transducer, characterized in that it is obtained from the process for the manufacture of a ceramic or of a glass as claimed in [one of claims 10 to 15] claim 10.

20. (Amended) A ferroelectric memory, characterized in that it is obtained from the process for the manufacture of a ceramic or of a glass as claimed in [one of claims 10 to 15] claim 10.--

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